

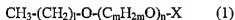
AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1. (currently amended): An active component for a cleaning solution for semiconductor substrates consisting essentially of a nonionic surface active agent represented by the following formula (1), a chelating agent, and a chelating accelerator, and at least one additive selected from the group consisting of a corrosion inhibitor for metal, an anionic surface active agent, cationic surface active agent, nonionic surface active agent, dispersing agent and anti-foaming agent,

wherein formula (1) is:



wherein l, m and n independently represent a positive number, and X represents a hydrogen atom or a hydrocarbon group, and

wherein a starting material of the oleophilic group portion, $\text{CH}_3-(\text{CH}_2)_l-$, is a primary alcohol and l is 9-11.

2. (canceled).

3. (currently amended): A-The active component for a cleaning solution according to claim 1, wherein m is 2 and n is 5-10.

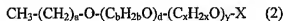
4. (currently amended): An active component for a cleaning solution for semiconductor substrates consisting of a nonionic surface active agent represented by the following formula (1),

a nonionic surface active agent represented by the following formula (2), a chelating agent, a chelating accelerator, and at least one additive selected from the group consisting of a corrosion inhibitor for metal, an anionic surface active agent, cationic surface active agent, nonionic surface active agent, dispersing agent and anti-foaming agent, wherein formula (1) is:



wherein l, m and n independently represent a positive number, and X represents a hydrogen atom or a hydrocarbon group, and

wherein a starting material of the oleophilic group portion, $\text{CH}_3-(\text{CH}_2)_l-$, is a primary alcohol and l is 9-11. A cleaning solution for semiconductor substrates according to claim 1 or claim 3, which further comprises a nonionic surface active agent represented by the following and wherein formula (2) is:



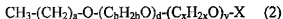
wherein a, b, d, x and y independently represent a positive number, b and x are different, and X represents a hydrogen atom or a hydrocarbon group, and

wherein the starting material of the oleophilic group portion, $\text{CH}_3-(\text{CH}_2)_a-$, is a primary alcohol and a is 9-11.

5. (canceled).

6. (currently amended): A-The active component for a cleaning solution according to claim 4, wherein b is 2, x is 3-5, d is 10 or less and y is 5 or less.

7. (currently amended): ~~An active component for a~~A cleaning solution for semiconductor substrates consisting ~~essentially~~ of a nonionic surface active agent represented by the formula (2), a chelating agent, ~~and a chelating accelerator, and at least one additive selected from the group consisting of a corrosion inhibitor for metal, an anionic surface active agent, cationic surface active agent, nonionic surface active agent, dispersing agent and anti-foaming agent,~~ wherein formula (2) is:



wherein a, b, d, x and y independently represent a positive number, b and x are different, and X represents a hydrogen atom or a hydrocarbon group, and

wherein the starting material of the oleophilic group portion, $\text{CH}_3-(\text{CH}_2)_a-$, is a primary alcohol and a is 9-11.

8. (canceled).

9. (currently amended): ~~A-The active component for a~~cleaning solution according to claim 7, wherein b is 2, x is 3-5, d is 10 or less and y is 5 or less.

10. (canceled).

11. (currently amended): ~~A-The active component for a~~cleaning solution according to claims ~~1, 4 or 7~~1-10, wherein the chelating agent is at least one compound selected from the group consisting of ethylenediaminetetraacetic acid, oxalic acid, ammonium oxalate, 1-

hydroxyethylidenediphosphonic acid, citric acid, ammonium citrate, catechol, ethylenediaminediortho-hydroxyphenylacetic acid [EDDHA], 8-quinolinol, and tropolone.

12-13. (canceled).

14. (currently amended): ~~A-The active component for a cleaning solution according to claims 1, 4 or 7-13, wherein the chelating accelerator contains a hydroxide and a fluoride or a salt thereof and wherein the hydroxide is at least one compound selected from the group consisting of ammonium hydroxide, tetramethylammonium hydroxide and choline.~~

15. (currently amended): ~~A-The active component for a cleaning solution according to claims 1, 4 or 7-12, wherein the chelating accelerator contains a hydroxide and a fluoride or a salt thereof and wherein and the fluoride or salt thereof is hydrofluoric acid or ammonium fluoride.~~

16-21. (canceled).